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PPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO
10/736,709	12/17/2003	Yong-Sung Ham	0630-1835P	5806
2292	7590 06/30/2005		EXAM	INER
BIRCH STE	WART KOLASCH &	CHACKO DAVIS, DABORAH		
FALLS CHURCH, VA 22040-0747			ART UNIT	PAPER NUMBER
	•		1756	

DATE MAILED: 06/30/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)			
Office Action Summer.	10/736,709	HAM, YONG-SUNG			
Office Action Summary	Examiner	Art Unit			
	Daborah Chacko-Davis	1756			
The MAILING DATE of this communication a Period for Reply	appears on the cover sheet v	vith the correspondence address			
A SHORTENED STATUTORY PERIOD FOR REI THE MAILING DATE OF THIS COMMUNICATION  - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication.  - If the period for reply specified above is less than thirty (30) days, a  - If NO period for reply is specified above, the maximum statutory peri  - Failure to reply within the set or extended period for reply will, by sta Any reply received by the Office later than three months after the may earned patent term adjustment. See 37 CFR 1.704(b).	N. 1.136(a). In no event, however, may a reply within the statutory minimum of thicod will apply and will expire SIX (6) MO state, cause the application to become A	reply be timely filed irty (30) days will be considered timely. NTHS from the mailing date of this communication. BANDONED (35 U.S.C. § 133).			
Status					
1) Responsive to communication(s) filed on 17	7 December 2003.	•			
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3) Since this application is in condition for allow	l				
closed in accordance with the practice unde	closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.				
Disposition of Claims					
4) ☐ Claim(s) 1-18 is/are pending in the application 4a) Of the above claim(s) is/are withd 5) ☐ Claim(s) is/are allowed.  6) ☐ Claim(s) 1-18 is/are rejected.  7) ☐ Claim(s) is/are objected to.  8) ☐ Claim(s) are subject to restriction and	Irawn from consideration.				
Application Papers					
9) The specification is objected to by the Exami	iner.				
10)☐ The drawing(s) filed on is/are: a)☐ accepted or b)☐ objected to by the Examiner.					
Applicant may not request that any objection to the	he drawing(s) be held in abeya	nce. See 37 CFR 1.85(a).			
Replacement drawing sheet(s) including the corr		• • • • • • • • • • • • • • • • • • • •			
11)☐ The oath or declaration is objected to by the	Examiner. Note the attache	d Office Action or form PTO-152.			
Priority under 35 U.S.C. § 119					
12) Acknowledgment is made of a claim for forei     a) All b) Some * c) None of:     1. Certified copies of the priority docume     2. Certified copies of the priority docume     3. Copies of the certified copies of the priority docume     application from the International Bure     * See the attached detailed Office action for a lie.	ents have been received. ents have been received in a riority documents have beer eau (PCT Rule 17.2(a)).	Application No n received in this National Stage			
Attachment(s)  1) Notice of References Cited (PTO-892)  2) Notice of Draftsperson's Patent Drawing Review (PTO-948)  3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/C Paper No(s)/Mail Date 12/03.	Paper No	Summary (PTO-413) (s)/Mail Date Informal Patent Application (PTO-152) 			

## **DETAILED ACTION**

## Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 2. Claims 1-18, are rejected under 35 U.S.C. 102(e) as being anticipated by U. S. Patent Application Publication No. 2003/0124865 (Baek et al).

Baek, in [0010], [0015], [0016], [0017], [0029], [0030], [0031], [0033], [0034], [0035], and in figures 3A through 3D, discloses a method of forming a pattern comprising providing a substrate wherein a plurality of panels and process-subjected layers are formed, wherein the substrate includes plurality of areas (forming display panels on a large area of the substrate), providing a cliché with recesses (plurality of grooves), filling the recesses with resist, and transferring the resist formed in the recesses of the cliché to the process-subjected layer of the substrate by using a printing roll (transfer roll), with the same width (desired size) as that of the panel in the display device (substrate area), that rotates and contacts the surface of the cliché, and transferring the blanket of the resist formed on the transfer roll to the process-subjected layer by rotating and contacting the surface of the process-subjected layer (claims 1-3,

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5, 11-12, 17, and 18). Baek, in [0017], [0033], [0034], [0035], discloses that the length of the resist to be transferred (blanket) is the same as the circumference of the transfer roll which in turn is the same as the length of the panel (divided area of the substrate) (claims 4, 13). Baek, in [0034], and [0035], discloses that the cliché, and the transfer roll have the same size as that of the panel (divided area of the substrate) (claims 6-7). Baek, in [0031], [0035], discloses that the process-subjected layer (etching object layer) may be a metal layer, or a semiconducting layer or an insulating layer such as SiOx or SiNx (claims 8-10, 14-16).

## Conclusion

3. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Daborah Chacko-Davis whose telephone number is (571) 272-1380. The examiner can normally be reached on M-F 9:30 - 6:00. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark F Huff can be reached on (571) 272-1385. The fax phone number for the organization where this application or proceeding is assigned is (703) 872-9306. Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you

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have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

OW o

June 27, 2005.

JOHN A. MCPHERSON PRIMARY EXAMINER